

EAST Search History

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L2	863	703/6.ccls.	US-PGPUB; USPAT; EPO; DERWENT	OR	OFF	2007/02/27 16:25

EAST Search History

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L1	46	local adj flare	US-PGPUB; USPAT; EPO; DERWENT	OR	OFF	2007/02/27 17:15
L2	4	("20030068565" "20040021854" "20040196447" "6233056").PN.	US-PGPUB; USPAT; USOCR	OR	OFF	2007/02/27 17:32
L3	4573	flar\$3 and mask	US-PGPUB; USPAT; EPO; DERWENT	OR	OFF	2007/02/27 17:33
L4	1367	L3 and (lithography or photolithography)	US-PGPUB; USPAT; EPO; DERWENT	OR	OFF	2007/02/27 17:35
L6	364	L4 and (OPC or correction)	US-PGPUB; USPAT; EPO; DERWENT	OR	OFF	2007/02/27 17:52
L7	4	("20040205688" "20050055658" "6303253" "6763514").PN.	US-PGPUB; USPAT; USOCR	OR	OFF	2007/02/27 18:16

Scholar All articles Recent articles

Results 1 - 10 of about 73 for "local flare". (0.08 seconds)

All Results

Did you mean: "[local flair](#)"

[R Hynes](#)

[K Nandra](#)

[E Gotthelf](#)

[E Robinson](#)

[L Ericsson](#)

[Effectiveness and confirmation of local area flare measurement method in various pattern layouts - group of 3 »](#)

D Nam, E Lee, S Jung, YS Kang, G Yeo, J Lee, H Cho ... - Proc. SPIE, 2002 - spie.org
... The LOAFER is designed to measure the local area flare of the lens, that is, the short and mid-range flare and the **local flare** distribution of the exposure ...

[Cited by 4](#) - [Related Articles](#) - [Cached](#) - [Web Search](#)

[Development of 157-nm full-field scanners - group of 3 »](#)

H Hata, H Nogawa, S Suda - Proceedings of SPIE, 2004 - link.aip.org
... When compared to ArF, **local flare** increases significantly. However, it has been confirmed that **local flare** can be greatly mitigated ...

[Cited by 3](#) - [Related Articles](#) - [Web Search](#)

[Local flare effects and correction in ArF lithography - group of 2 »](#)

T Yao, M Osawa, T Minami, N Yamamoto, H Aoyama, G ... - VLSI Technology, 2003. Digest of Technical Papers. 2003 ..., 2003 - ieeexplore.ieee.org

Page 1. 4B-1 **Local Flare** Effects and Correction in ArF Lithography Teruyoshi Yao, Morimi Osawa, Takayoshi Mind, Norihiro Yamamoto, Hajime Aoyama, Genshi Okuda, ...

[Cited by 1](#) - [Related Articles](#) - [Web Search](#)

[Unsteady Aerodynamics of an Ablating Flared Body of Revolution Including Effect of Entropy Gradient - group of 2 »](#)

LE Ericsson - AZAA Journal, 1968 - pdf.aiaa.org
... **local flare** forces become dynamically destabilizing. ... 2 and the **local "flare efficiency"** type of effects can easily be computed. It ...

[Cited by 8](#) - [Related Articles](#) - [Web Search](#)

[Correction for local flare effects approximated with double Gaussian profile in ArF lithography - group of 4 »](#)

M Osawa, T Yao, H Aoyama, K Ogino, H Hoshino, Y ... - Journal of Vacuum Science & Technology B: Microelectronics ..., 2003 - link.aip.org

... been developed for correcting line width variations due to midrange flare with a scattering range of over a few tens of micrometers (which we call **local flare** ...

[Cited by 1](#) - [Related Articles](#) - [Web Search](#) - [BL Direct](#)

[Application of Realistic Model Atmospheres to Eclipse Maps of Accretion Disks: The Effective ... - group of 3 »](#)

EL Robinson, JH Wood, RA Wade - The Astrophysical Journal, 1999 - journals.uchicago.edu
... 4 1 at the outer edge, giving h/r . This latter relation yields a slope of

dh/dr 0.1 at the outer edge of the disk, corresponding to a **local flare** angle of ...

[Cited by 9](#) - [Related Articles](#) - [Web Search](#) - [BL Direct](#)

[The Properties of the Relativistic Iron K-Line in NGC 3516 - group of 7 »](#)

K Nandra, IM George, RF Mushotzky, TJ Turner, T ... - The Astrophysical Journal, 1999 - journals.uchicago.edu

... the variation in the blue wing could be due to an enhancement in the illuminating flux of the inner disk portion moving toward us, due to a **local flare** (cf. ...

[Cited by 117](#) - [Related Articles](#) - [Web Search](#) - [BL Direct](#)

[Relevance of TCAD to process-aware design - group of 6 »](#)

Scholar All articles Recent articles

Results 1 - 10 of about 47 for murai "area density". (0.07 seconds)

All Results

F Murai

H Yoda

Y Zheng

M Osawa

S Okazaki

Fast proximity effect correction method using a pattern area density map - group of 4 »

F Murai, H Yoda, S Okazaki, N Saitou, Y Sakitani - Journal of Vacuum Science & Technology B:

Microelectronics ..., 1992 - link.aip.org

... using a pattern area density map. [Journal of Vacuum Science & Technology B: Microelectronics and Nanometer Structures 10, 3072 (1992)]. Fumio Murai, Haruo Yoda ...

Cited by 17 - [Related Articles](#) - [Web Search](#) - [BL Direct](#)

Proximity effect correction using pattern shape modification and area density map for electron-beam ... - group of 4 »

M Osawa, K Takahashi, M Sato, H Arimoto, K Ogino, ... - Journal of Vacuum Science & Technology B: Microelectronics ..., 2001 - link.aip.org

Proximity effect correction using pattern shape modification and area density map for electron-beam projection lithography. [Journal ...

Cited by 9 - [Related Articles](#) - [Web Search](#) - [BL Direct](#)

Pattern fabrication method using a charged particle beam and apparatus for realizing same - group of 5 »

H Yoda, F Murai - US Patent 5,278,421, 1994 - Google Patents

... ACHARGED PARTICLE BEAM AND APPARATUS FOR REALIZING SAME [75] Inventors: Haruo Yoda; Fumio Murai, both of ... posed is extremely small and that the area density ...

Cited by 7 - [Related Articles](#) - [Web Search](#)

Greater number of microtubules per axon of unmyelinated fibers of mutant quails deficient in ... - group of 3 »

..., M Mizutani, T Yamamoto, H Hayashi, Y Murai - Acta Neuropathologica, 1994 - Springer

... JX Zhao - A. Ohnishi () 9 T. Yamamoto 9 Y. Murai Department of Neurology; University of ... NF per axon and per m² of the transverse axonal area (density) were cal ...

Cited by 6 - [Related Articles](#) - [Web Search](#) - [BL Direct](#)

Variation in bone mineral density of the sacrum in young adults and its significance for sacral ... - group of 4 »

Y Zheng, WW Lu, Q Zhu, L Qin, S Zhong, JC Leong - Spine, 2000 - spinejournal.com

... calculated from quantitative computed tomography (QCT), was used to obtain area density (g/cm³ ... Okuyama K, Sato K, Abe E, Inaba H, Shimada Y, Murai H. Stability ...

Cited by 16 - [Related Articles](#) - [Web Search](#) - [BL Direct](#)

Proximity effect correction using pattern shape modification and area density map - group of 4 »

K Takahashi, M Osawa, M Sato, H Arimoto, K Ogino, ... - Journal of Vacuum Science & Technology B: Microelectronics ..., 2000 - link.aip.org

... F. Murai, H. Yoda, S. Okazaki, N. Saitou, and Y. Sakitani, "Fast proximity effect correction method using a pattern area density map," J. Vac. Sci. ...

Cited by 3 - [Related Articles](#) - [Web Search](#) - [BL Direct](#)

Proximity-effect correction for EPL by using multiple pattern-area- density maps and pattern ... - group of 5 »

F Murai, H Fukuda, S Mori, A Sato, K Nakajo - Proceedings of SPIE, 2003 - spie.org

Abstract. PUBLICATIONS. Proximity-effect correction for EPL by using multiple pattern-area- density maps and pattern classification Murai, Fumio, Hitachi, Ltd. ...

Cited by 1 - [Related Articles](#) - [Cached](#) - [Web Search](#)

Image area discriminating system for an image processing apparatus - group of 2 »

☐ Search Results

BROWSE

SEARCH

IEEE XPLORE GUIDE

SUPPORT

Results for "(local flare)" <and> (pyr >= 1950 <and> pyr <= 2004)"

Your search matched 6 of 1513808 documents.

A maximum of 100 results are displayed, 25 to a page, sorted by Relevance in Descending order.

e-mail printer friendly

» Search Options

[View Session History](#)

[New Search](#)

Modify Search

(local flare)" <and> (pyr >= 1950 <and> pyr <= 2004)

Search

☐ Check to search only within this results set

Display Format: ☒ Citation ☐ Citation & Abstract

view selected items

[Select All](#) [Deselect All](#)

IEEE JNL IEEE Journal or Magazine
IET JNL IET Journal or Magazine
IEEE CNF IEEE Conference Proceeding
IET CNF IET Conference Proceeding
IEEE STD IEEE Standard

- ☐ 1. Local flare effects and correction in ArF lithography
Yao, T.; Osawa, M.; Minami, T.; Yamamoto, N.; Aoyama, H.; Okuda, G.; Sawano, T.; Kamatsuki, I.; Sugimoto, F.; Futatsuya, H.; Kobayashi, K.; Ogino, K.; Hoshino, H.; Machida, Y.; Arimoto, H.; Asai, S.;
[VLSI Technology, 2003. Digest of Technical Papers, 2003 Symposium on](#)
10-12 June 2003 Page(s):43 - 44
[AbstractPlus](#) | Full Text: [PDF](#)(258 KB) IEEE CNF
[Rights and Permissions](#)
- ☐ 2. Forward and Backward Scattered Modes in Multimode Nonuniform Transitions
Tang, C.C.H.;
[Microwave Theory and Techniques, IEEE Transactions on](#)
Volume 16, Issue 8, Aug 1968 Page(s):494 - 502
[AbstractPlus](#) | Full Text: [PDF](#)(744 KB) IEEE JNL
[Rights and Permissions](#)
- ☐ 3. Test structure for fixing OPC of 200 nm pitch via chain using inner and outer dummy via array
Nasuno, T.; Matsubara, Y.; Minami, A.; Uchida, N.; Kobayashi, H.; Aoyama, H.; Tsuda, H.; Tsujita, K.; Wakamiya, W.; Kobayashi, N.;
[Microelectronic Test Structures, 2004. Proceedings. ICMTS '04. The International Conference on](#)
22-25 March 2004 Page(s):23 - 28
[AbstractPlus](#) | Full Text: [PDF](#)(563 KB) IEEE CNF
[Rights and Permissions](#)
- ☐ 4. Intense electron beam propagation by charge neutralization from a dielectric collimator
Vijayan, T.; Roychowdhury, P.; Iyyengar, S.K.;
[Plasma Science, IEEE Transactions on](#)
Volume 22, Issue 2, April 1994 Page(s):199 - 204
Digital Object Identifier 10.1109/27.279023
[AbstractPlus](#) | Full Text: [PDF](#)(464 KB) IEEE JNL
[Rights and Permissions](#)
- ☐ 5. 2003 Symposium on VLSI Technology. Digest of Technical Papers (IEEE Cat. No.03CH37407)
[VLSI Technology, 2003. Digest of Technical Papers, 2003 Symposium on](#)
10-12 June 2003
[AbstractPlus](#) | Full Text: [PDF](#)(461 KB) IEEE CNF
[Rights and Permissions](#)
- ☐ 6. "SIG-NABOUT"-the development and trial of a novel junction design
Webb, P.J.;
[Road Traffic Monitoring and Control, 1994., Seventh International Conference on](#)
26-28 Apr 1994 Page(s):106 - 110
[AbstractPlus](#) | Full Text: [PDF](#)(232 KB) IET CNF

Scholar All articles Recent articles

Results 1 - 10 of about 34 for **flare simulation opc**. (0.11 seconds)

All Results

[A Erdmann](#)

[M McKean](#)

[A Ray-Chaudhuri...](#)

[R Winglee](#)

[G Dulk](#)

Model-based OPC/DRC considering local flare effects - group of 3 »

H Futatsuya, T Yao, M Osawa, K Ogino, H Hoshino, H ... - Proceedings of SPIE, 2004 - link.aip.org
... including local **flare** effects, and its results. The **simulation** results show good agreement with the experimental results, indicating that effective **OPC/DRC** ...

[Web Search](#)

New process models for OPC at sub-90-nm nodes - group of 6 »

Y Granik, NB Cobb - Proceedings of SPIE, 2003 - perso.enst-bretagne.fr
... Optical **flare** CMPnon- uniformity Illuminator optics ... Outside of the modeling range, the target bias **OPC** will be used PRINTimage **simulation** contours Figure 10. ...

[Cited by 3](#) - [Related Articles](#) - [View as HTML](#) - [Web Search](#)

Relevance of TCAD to process-aware design - group of 6 »

VK Singh, J Garcia-Colevatti - Proceedings of the SPIE, 2002 - uos.ac.kr
... Impact of aberrations on design - Layout dependent **flare** in EUV ... **simulation** Page 20.
TCAD ... models to build/strengthen **OPC** models Complexity Run time Aerial ...

[Cited by 1](#) - [Related Articles](#) - [View as HTML](#) - [Web Search](#)

Relevance of technology computer aided design (TCAD) to process-aware design

V Singh, J Garcia-Colevatti - Journal of Microlithography, Microfabrication, and ..., 2002 - link.aip.org
... with one of the areas within TCAD, lithography **simulation**. ... In addition to **OPC** and the short-range effects ... such effects are lens aberrations and **flare**, with the ...

[Related Articles](#) - [Web Search](#) - [BL Direct](#)

Transistor flaring in deep submicron-design considerations - group of 5 »

V Singhal, CB Keshav, KG Sumanth, PR Suresh - Design Automation Conference, 2002. Proceedings of ASP-DAC ..., 2002 - ieeexplore.ieee.org

... 4.1 Designing out **flares**- A solution for high ... Our analysis with statistical **simulation** results showed that we ... Most **OPC** based corrective schemes, which involve ...

[Related Articles](#) - [Web Search](#)

Limits of strong phase-shift patterning for device research - group of 7 »

M Fritze, RD Mallen, B Wheeler, D Yost, JP Snyder, ... - Proceedings of SPIE, 2003 - photonics.com
... test cells, no clear influence of long range **flare** ... Fig 6: IC Workbench aerial image **simulation** of transistor gate with and without **OPC** described in ...

[Cited by 3](#) - [Related Articles](#) - [View as HTML](#) - [Web Search](#)

Propagation and absorption of electron-cyclotron maser radiation during solar flares - group of 4 »

ME McKean, RM Winglee, GA Dulk - Solar Physics, 1989 - Springer
... could provide the heating necessary to explain some soft X-ray features observed in solar **flares**. ... $0 = 90$, $\text{opc}/12 \text{ e} = 0.3$, $\text{oph}/2 \text{ e} = 0.03$, and $L_s = 105 \text{ km}$

[Cited by 30](#) - [Related Articles](#) - [Web Search](#)

Potential issues on optical proximity correction (OPQ) using double dipole lithography

TB Chiou, S Hsu, M Eurlings, E Hendrickx, A Chen - Microprocesses and Nanotechnology Conference, 2004. Digest ..., 2004 - ieeexplore.ieee.org

... to describe the short- and mid-range **flare** as a ... be used as an input parameter in the lithography **simulator**. ... is able to improve the accuracy of **OPC** calibration. ...

[Related Articles](#) - [Web Search](#)

Comparison of simulation approaches for chemically amplified resists - group of 5 »

A Erdmann, W Henke, S Robertson, E Richter, B ... - Proc. SPIE, 2001 - sigma-c.de

Scholar [All articles](#) [Recent articles](#)

Results 1 - 10 of about 97 for **flare opc**. (0.18 seconds)

All Results

[R Winglee](#)

[G Dulk](#)

[B Lin](#)

[M McKean](#)

[M Endl](#)

Correction for local flare effects approximated with double Gaussian profile in ArF lithography - group of 4 »

M Osawa, T Yao, H Aoyama, K Ogino, H Hoshino, Y ... - Journal of Vacuum Science & Technology B: Microelectronics ..., 2003 - link.aip.org

... to local **flare** intensity and is independent of pattern layout considering the order of the local **flare** correction (LFC) and optical proximity correction (OPC). ...

[Cited by 1](#) - [Related Articles](#) - [Web Search](#) - [BL Direct](#)

Model-based OPC/DRC considering local flare effects - group of 3 »

H Futatsuya, T Yao, M Osawa, K Ogino, H Hoshino, H ... - Proceedings of SPIE, 2004 - link.aip.org

... OPC/DRC using this method is possible. Model-based OPC/DRC considering local **flare** effects. [Proceedings of SPIE 5377, 451 (2004)]. ...

[Web Search](#)

[CITATION] Model-based OPC/DRC considering local flare effects [5377-40]

H Futatsuya, T Yao, M Osawa, K Ogino, H Hoshino, H ... - PROCEEDINGS-SPIE THE INTERNATIONAL SOCIETY FOR OPTICAL ..., 2004 - International Society for Optical Engineering; 1999

[Web Search](#) - [BL Direct](#)

Investigation of stray light characteristic by multiple Gaussian modeling and its OPC application - group of 3 »

HC Kim, DS Nam, GS Yeo, SJ Lee, SG Woo, HK Cho, WS ... - Proceedings of SPIE, 2004 - link.aip.org

... scattering range characteristic of **flare**. To minimize CD errors from OPC, **flare** level and EOR should be considered in the OPC procedure. ...

[Web Search](#)

Relevance of TCAD to process-aware design - group of 6 »

VK Singh, J Garcia-Colevatti - Proceedings of the SPIE, 2002 - uos.ac.kr

... ò Focus on aspects of Lithography – Design coupling – Some challenges in OPC – Impact of aberrations on design – Layout dependent **flare** in EUV ...

[Cited by 1](#) - [Related Articles](#) - [View as HTML](#) - [Web Search](#)

... of techniques to measure the point spread function due to scatter and flare in EUV lithography ... - group of 4 »

M Chandhok, SH Lee, CG Krautschik, G Zhang, BJ ... - Proceedings of SPIE, 2004 - spie.org

... expected that to meet the CD control requirements for the 32 nm node, **Flare** Variation Compensation (FVC), akin to Optical Proximity Correction (OPC) would be ...

[Cited by 4](#) - [Related Articles](#) - [Cached](#) - [Web Search](#)

Test structure for fixing OPC of 200 nm pitch via chain using inner and outer dummy via array - group of 2 »

T Nasuno, Y Matsubara, A Minami, N Uchida, H ... - Microelectronic Test Structures, 2004. Proceedings. ICMTS'04 ..., 2004 - ieeeexplore.ieee.org

... width and length of dummy patterns are shrunk drastically by OPE and local **flare** effect. However, inner pattern can be protected. In the case of OPC A, length ...

[Related Articles](#) - [Web Search](#)

New process models for OPC at sub-90-nm nodes - group of 6 »

Y Granik, NB Cobb - Proceedings of SPIE, 2003 - perso.enst-bretagne.fr

... hard because the **flare** has long interaction range, which results in the destruction of the design hierarchy and consequential explosion of OPC runtime. ...

[Cited by 3](#) - [Related Articles](#) - [View as HTML](#) - [Web Search](#)

Scholar All articles Recent articles

Results 1 - 10 of about 18 for **flare calculation opc**. (0.14 seconds)

All Results

M Endl

F Rouesnel

S Els

A Kaufer

S Brillant

Correction for local **flare** effects approximated with double Gaussian profile in ArF lithography - group of 4 »

M Osawa, T Yao, H Aoyama, K Ogino, H Hoshino, Y ... - Journal of Vacuum Science & Technology B: Microelectronics ..., 2003 - link.aip.org

... The CD variation due to local **flare** was reduced from 22 ... GB of memory each) were used to **calculate** each process ... processing times are much faster than the **OPC** ones ...

Cited by 1 - [Related Articles](#) - [Web Search](#) - [BL Direct](#)

Propagation and absorption of electron-cyclotron maser radiation during solar flares - group of 4 »

ME McKean, RM Winglee, GA Dulk - Solar Physics, 1989 - Springer

... to explain some soft X-ray features observed in solar **flares**. ... $0 = 90$, **opc**/12 e = 0.3, $\text{oph}/2 \text{ e} = 0.03$... Plotted are: Equation (11) (solid line) and numerical ...

Cited by 30 - [Related Articles](#) - [Web Search](#)

Relevance of TCAD to process-aware design - group of 6 »

VK Singh, J Garcia-Colevatti - Proceedings of the SPIE, 2002 - uos.ac.kr

... Focus on aspects of Lithography - Design coupling - Some challenges in **OPC** - Impact of aberrations on design - Layout dependent **flare** in EUV ...

Cited by 1 - [Related Articles](#) - [View as HTML](#) - [Web Search](#)

Orientation dependent shielding for use with dipole illumination techniques

DFUSUS HSU, NUS CORCORAN, JFUS CHEN - EP Patent 1,385,052, 2004 - freepatentsonline.com

... and horizontal mask patterns and application of **OPC** techniques as ... The percentage of **flare** was calculated using the following equation: Straylight % = E_0 ...

[Cached](#) - [Web Search](#)

High numerical aperture lithographic imagery at the Brewster angle

TA Brunner, N Seong, WD Hinsberg, JA Hoffnagle, FA ... - Journal of Microlithography, Microfabrication, and ..., 2002 - link.aip.org

... by the pupil edge, defocus effects, image **flare** effects, stage ... mask will need more accurate **calculation** than that ... for optical proximity correction (**OPC**) methods ...

Cited by 7 - [Related Articles](#) - [Web Search](#) - [BL Direct](#)

The low-level radial velocity variability in Barnard's star (= GJ 699) - group of 5 »

M Kürster, M Endl, F Rouesnel, S Els, A Kaufer, S ... - A&A, 2003 - aanda.org

... For all data used in our **calculation** (Hip = Hipparcos, Nid = Nidever et al. ... H index (middle spectrum offset by 0.5 flux units), and the **flare** event (upper ...

Cited by 22 - [Related Articles](#) - [Cached](#) - [Web Search](#) - [BL Direct](#)

The low-level radial velocity variability in Barnard's star (= GJ 699) - group of 6 »

M Kürster, M Endl, F Rouesnel, S Els, A Kaufer, S ... - A&A, 2003 - edpsciences.org

... For all data used in our **calculation** (Hip = Hipparcos, Nid = Nidever et al. ... H α index (middle spectrum offset by 0.5 flux units), and the **flare** event (upper ...

Cited by 18 - [Related Articles](#) - [Web Search](#)

Enhancements in rigorous simulation of light diffraction from phase-shift masks - group of 4

»

A Erdmann, N Kachwala - Proc. SPIE, 2002 - sigma-c.de

... thin masks there is no necessity to perform a new **calculation** of the ... This occurs for subresolution features on optical proximity corrected (**OPC**) masks, for ...

Cited by 4 - [Related Articles](#) - [Web Search](#)

☐ Search Results

[BROWSE](#)

[SEARCH](#)

[IEEE XPLORE GUIDE](#)

[SUPPORT](#)

Results for "((flar*<and>opc)) <and> (pyr >= 1964 <and> pyr <= 2004)"

Your search matched 8 of 1513808 documents.

A maximum of 100 results are displayed, 25 to a page, sorted by Relevance in Descending order.

 e-mail  printer friendly

» Search Options

[View Session History](#)

[New Search](#)

Modify Search

((flar*<and>opc)) <and> (pyr >= 1964 <and> pyr <= 2004)

[Search](#) >

☐ Check to search only within this results set

Display Format:

☒ Citation

☐

Citation & Abstract

[view selected items](#)

[Select All](#) [Deselect All](#)

» Key

IEEE JNL	IEEE Journal or Magazine
IET JNL	IET Journal or Magazine
IEEE CNF	IEEE Conference Proceeding
IET CNF	IET Conference Proceeding
IEEE STD	IEEE Standard

- ☐ 1. Test structure for fixing OPC of 200 nm pitch via chain using inner and outer dummy via array
 Nasuno, T.; Matsubara, Y.; Minami, A.; Uchida, N.; Kobayashi, H.; Aoyama, H.; Tsuda, H.; Tsujita, K.; Wakamiya, W.; Kobayashi, N.;
[Microelectronic Test Structures, 2004. Proceedings. ICMTS '04. The International Conference on](#)
 22-25 March 2004 Page(s):23 - 28
[AbstractPlus](#) | Full Text: [PDF\(563 KB\)](#) IEEE CNF
[Rights and Permissions](#)
- ☐ 2. Transistor flaring in deep submicron-design considerations
 Singhal, V.; Keshav, C.B.; Sumanth, K.G.; Suresh, P.R.;
[Design Automation Conference, 2002. Proceedings of ASP-DAC 2002. 7th Asia and South Pacific and the 15th](#)
[International Conference on VLSI Design. Proceedings.](#)
 7-11 Jan. 2002 Page(s):299 - 304
 Digital Object Identifier 10.1109/ASPAC.2002.994938
[AbstractPlus](#) | Full Text: [PDF\(1113 KB\)](#) IEEE CNF
[Rights and Permissions](#)
- ☐ 3. FPGA as Process Monitor-an effective method to characterize poly gate CD variation and its impact on product performance and yield
 Xiao-Yu Li; Feng Wang; La, T.; Zhi-Min Ling;
[Semiconductor Manufacturing, IEEE Transactions on](#)
 Volume 17, Issue 3, Aug. 2004 Page(s):267 - 272
 Digital Object Identifier 10.1109/TSM.2004.831934
[AbstractPlus](#) | [References](#) | Full Text: [PDF\(1080 KB\)](#) IEEE JNL
[Rights and Permissions](#)
- ☐ 4. A redundancy method of AS traffic in signaling gateway using loadsharing scheme
 Hyunjeong Lee; Byungsun Lee;
[Advanced Communication Technology, 2004. The 6th International Conference on](#)
 Volume 2, 2004 Page(s):833 - 837
 Digital Object Identifier 10.1109/ICACT.2004.1292986
[AbstractPlus](#) | Full Text: [PDF\(394 KB\)](#) IEEE CNF
[Rights and Permissions](#)
- ☐ 5. An effective method of characterization poly gate CD variation and its impact on product performance and yield
 Xiao-Yu Li; Feng Wang; Tho La; Zhi-Min Ling; Ji-Fu Kung; Wang, M.H.; Hong Nan Chen; Chia-Pin Lee;
[Semiconductor Manufacturing, 2003 IEEE International Symposium on](#)
 30 Sept.-2 Oct. 2003 Page(s):259 - 262
[AbstractPlus](#) | Full Text: [PDF\(405 KB\)](#) IEEE CNF
[Rights and Permissions](#)
- ☐ 6. A pattern matching system for linking TCAD and EDA
 Gennari, F.E.; Neureuther, A.R.;
[Quality Electronic Design, 2004. Proceedings. 5th International Symposium on](#)

Search

Advanced Search

BROWSE PROCEEDINGS

- ☒ Proceedings
 - ☐ By Year
 - ☐ By Symposium
 - ☐ By Volume No.
 - ☐ By Volume Title
 - ☐ By Technology

BROWSE JOURNALS

- ☒ Journals
 - ☐ Optical Engineering
 - ☐ J. Electronic Imaging
 - ☐ J. Biomedical Optics
 - ☐ J. Micro/Nanolithography, MEMS, and MOEMS
 - ☐ J. Applied Remote Sensing
 - ☐ J. Nanophotonics

SUBSCRIPTIONS & PRICING

- ☒ Institutions & Corporations
- ☒ Personal subscriptions

GENERAL INFORMATION

- ☒ About the Digital Library
- ☒ Terms of Use
- ☒ SPIE Home

Search Results

You were searching for : (flare) **ETSA** ²

You found 368 out of 233957 (368 returned)
Documents 1 - 25 listed on this page

Refine your query if desired:

AND

in

Refine

Results Sorting Options

Relevance Order

Re-sort

[Related SPIE Products]

[1 | 2 | 3 | 4 | 5 | 6 | 7 | 8 | 9 | 10 | Next 25 | More Results]

97%

1. ☐ **Effectiveness and confirmation of local area flare measurement method in various pattern layouts**
Dongseok Nam, Eunmi Lee, Sung-gon Jung, Young S. Kang, Gisung Yeo, Junghyun Lee, Hanku Cho, Woo-Sung Han, and Joo-Tae Moon
Proc. SPIE **4691**, 57 (2002) Full Text: [PDF (803 kB)] (10 pages)

94%

2. ☐ **Anisotropic EUV flare measured in the engineering test stand (ETS)**
Sang Hun Lee, Manish Chandhok, Christof Krautschik, and Michael Goldstein
Proc. SPIE **5374**, 818 (2004) Full Text: [PDF (76 kB)] (6 pages)

94%

3. ☐ **Across field and across wafer flare: from KrF stepper to ArF scanner**
Yorick Trouiller, Emmanuelle Luce, Alexandra Barberet, L. Depre, and Patrick Schiavone
Proc. SPIE **4000**, 880 (2000) Full Text: [PDF (4632 kB)] (12 pages)

93%

4. ☐ **Model-based OPC/DRC considering local flare effects**
Hiroki Futatsuya, Teruyoshi Yao, Morimi Osawa, Kozo Ogino, Hiromi Hoshino, Hiroshi Arimoto, Yasuhide Machida, and Satoru Asai
Proc. SPIE **5377**, 451 (2004) Full Text: [PDF (187 kB)] (8 pages)

92%

5. ☐ **Measurement of the flare and in-field linewidth variation due to the flare**
Tae Moon Jeong, Seong-Woon Choi, Sang-Gyun Woo, Woo-Sung Han, and Jung-Min Sohn
Proc. SPIE **4691**, 1465 (2002) Full Text: [PDF (463 kB)] (9 pages)

92%

6. ☐ **Comparison of techniques to measure the point spread function due to scatter and flare in EUV lithography systems**
Manish Chandhok, Sang H. Lee, Christof G. Krautschik, Guojing Zhang, Bryan J. Rice, Michael Goldstein, Eric Panning, Robert Bristol, Alan R. Stivers, and Melissa Shell
Proc. SPIE **5374**, 854 (2004) Full Text: [PDF (100 kB)] (7 pages)

91%

7. ☐ **Measuring and modeling flare in optical lithography**
Chris A. Mack
Proc. SPIE **5040**, 151 (2003) Full Text: [PDF (88 kB)] (11 pages)

90%

8. ☐ **Flare effect of different shape of illumination apertures in 193nm optical lithography system**
Young-Je Yun, Ju-Hyung Moon, Haeng-Leem Jeon, Jea-Hee Kim, and Keeho Kim
Proc. SPIE **6154**, 615435 (2006) Full Text: [PDF (531 kB)] (7 pages)

SEARCH DIGITAL LIBRARY

[Back to Search Query | Start New Search | Searching Hints]

Search

Advanced Search

BROWSE PROCEEDINGS

- ☒ Proceedings
 - ☐ By Year
 - ☐ By Symposium
 - ☐ By Volume No.
 - ☐ By Volume Title
 - ☐ By Technology

BROWSE JOURNALS

- ☒ Journals
 - ☐ Optical Engineering
 - ☐ J. Electronic Imaging
 - ☐ J. Biomedical Optics
 - ☐ J. Micro/Nanolithography, MEMS, and MOEMS
 - ☐ J. Applied Remote Sensing
 - ☐ J. Nanophotonics

SUBSCRIPTIONS & PRICING

- ☒ Institutions & Corporations
- ☒ Personal subscriptions

GENERAL INFORMATION

- ☒ About the Digital Library
- ☒ Terms of Use
- ☒ SPIE Home

Search Results

You were searching for : (flare) <and> (model* <IN> (abstract,title,keywords))  

You found 91 out of 368 (91 returned)
Documents 51 - 75 listed on this page

Refine your query if desired:

AND

in Abstract/Title/Keywords Refine

Results Sorting Options

Relevance Order

Re-sort

[Related SPIE Products]

[Previous 25 | 1 | 2 | 3 | 4 | Next 25]

77%

51. ☐ **Assessing the impact of real world manufacturing lithography variations on post-OPC CD control**
John L. Sturtevant, J. Word, P. LaCour, J. W. Park, and D. Smith
Proc. SPIE **5756**, 240 (2005) Full Text: [PDF (214 kB)] (15 pages)

77%

52. ☐ **Optimization of epitaxial layer design for high brightness tapered lasers**
J. M. G. Tijero, D. Rodriguez, L. Borruel, S. Sujecki, E. C. Larkins, and I. Esquivias
Proc. SPIE **5722**, 280 (2005) Full Text: [PDF (245 kB)] (8 pages)

77%

53. ☐ **Modeling countermeasures to imaging infrared seekers**
Laurence J. Cox, Michael A. Batten, Stephen R. Carpenter, and Philip A. B. Saddleton
Proc. SPIE **5615**, 112 (2004) Full Text: [PDF (462 kB)] (8 pages)

77%

54. ☐ **Bandwidth characteristics of corrugated waveguide-horn feeds for CMB experiments**
Emily Gleeson, William Lanigan, J. Anthony Murphy, Creidhe O'Sullivan, Bruno Maffei, Sarah E. Church, and Eoin Cartwright
Proc. SPIE **5498**, 713 (2004) Full Text: [PDF (257 kB)] (12 pages)

77%

55. ☐ **New concepts in OPC**
Nick Cobb and Yuri Granik
Proc. SPIE **5377**, 680 (2004) Full Text: [PDF (334 kB)] (11 pages)

77%

56. ☐ **Accurate gate CD control through the full-chip area using the dual model in the model-based OPC**
Ji-Suk Hong, Chul-Hong Park, Dong-Hyun Kim, Soo-Han Choi, Yong-Chan Ban, Yoo-Hyon Kim, Moon-Hyun Yoo, and Jeong-Taek Kong
Proc. SPIE **5377**, 571 (2004) Full Text: [PDF (225 kB)] (10 pages)

77%

57. ☐ **Evaluation of the critical dimension control requirements in the ITRS using statistical simulation and error budgets**
Scott D. Hector, Sergei V. Postnikov, and Jonathan Cobb
Proc. SPIE **5377**, 555 (2004) Full Text: [PDF (193 kB)] (16 pages)

77%

58. ☐ **Development of an accurate empirical model for ArF lithography**
Shoji Mimotogi, Daisuke Kawamura, Takashi Sato, and Soichi Inoue
Proc. SPIE **5377**, 1405 (2004) Full Text: [PDF (136 kB)] (8 pages)